

Product Name:

E3650 Mask MVM-SEM

Application/Main Usage:

Precision SEM supporting Sub-10nm Node Photomask

Short Description/Highlight:

The E3650 uses Advantest's proprietary electron beam scanning technology to measure fine pattern dimensions on photomasks with higher precision and stability. E3650's higher throughput enables massive measurement required by more complex patterning and increased number of masks due to multiple patterning. In addition to leading-edge photomasks, the new tool also demonstrates superior performance when measuring EUV masks and master templates for nanoimprint applications.

Features/Benefits

- Delivers massive measurement
- Provides high precision measurement (SRS scan, large current)
- Features large field measurement
- Supports DBM (Design Based Metrology)



Product Name:

E5610 Mask DR-SEM

Application/Main Usage:

Defect Review SEM supports next-generation photomasks.

Short Description/Highlight:

The E5610 is a MASK DR-SEM for reviewing and classifying ultra-small defects in photomask and blanks. The E5610 is expected to contribute to next-generation photomask production quality improvement and shorter manufacturing TAT.

Features/Benefits

- High Spatial Resolution
- High Stable, Fully Automatic Image Capture
- Compatible with Mask Inspection Systems
- Elemental Composition Analysis Option

